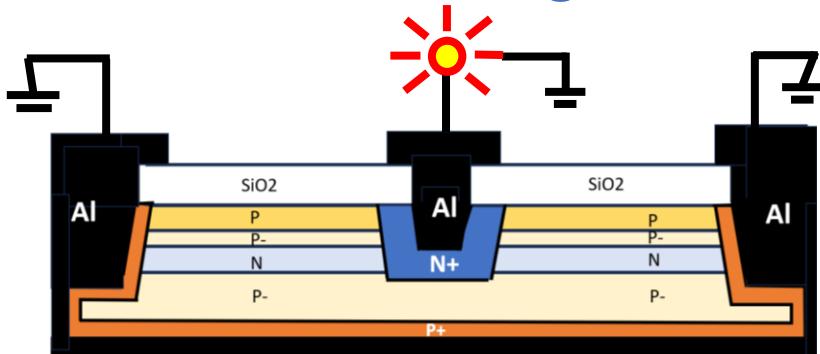
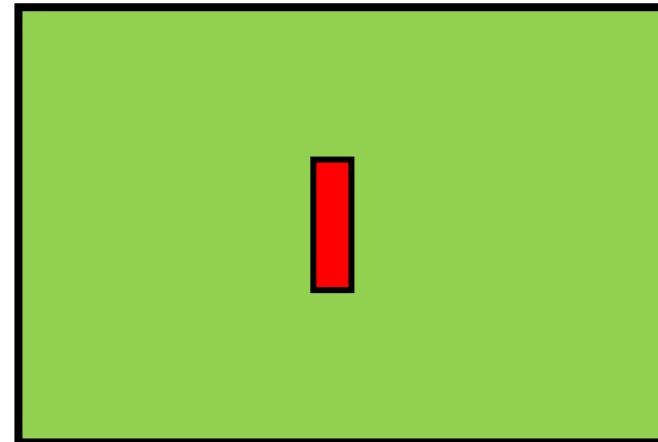


006 Mask 01 Setting for N+ Formation



Positive Photo Resist は光が照射した部分のみが溶液で解けて除去できます。



<https://lushbooklife.com/news-of-positive-photoresist/>

Metal Masking Plate 01

Metal Masking Plate 01

Positive Photo Resist

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